CLAIMS

1. A method comprising

measuring radiation reflected from a metrology target;

decomposing the measured radiation into components; and

applying a filter to the measured radiation, wherein the filter comprises an upper and a lower value, which defines an individual component.

2. A method according to claim 1, wherein decomposing the measured radiation is obtained with a Fourier transform of the measured radiation.

3. A method to measure a parameter of a lithographic process comprising

a) illuminating a metrology target with radiation,

b) detecting scattered radiation from the target,

c) changing a parameter of metrology apparatus,

d) repeating steps a) to c) for a multitude of values of the parameter of the metrology apparatus,

e) decomposing the measured radiation into components, and

f) applying a filter to the measured radiation, wherein the filter comprises an upper and a lower value, which defines an individual component.

4. A method according to claim 3, wherein the decomposition is a Fourier transform.

5. A method according to claim 3, wherein the method further comprises

selecting the components smaller than a threshold.

6. A method according to claim 5, wherein an overlay is generated using a reverse decomposition and utilizing only selected components.

7. A method to measure a parameter of a lithographic process comprising

a) illuminating a metrology target with radiation,

b) detecting scattered radiation from the target,

c) changing a parameter of metrology apparatus,

d) repeating steps a) to c) for a multitude of values of the parameter of the metrology apparatus,

e) decomposing the measurement obtained in step d) into individual components,

f) applying a filter to the measurement, and wherein the filter comprises an upper and a lower value, which defines an individual component.

8. A method according to claim 7, wherein the filter comprises an upper and a lower value, which defines an interval of components.

9. A method according to claim 7, wherein the filter is varied.